

Michael Murphy

List of Publications by Year in descending order

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Version: 2024-02-01

17
papers

143
citations

1478505

6
h-index

1281871

11
g-index

17
all docs

17
docs citations

17
times ranked

129
citing authors

#	ARTICLE	IF	CITATIONS
1	Polymerizable Olefins Groups in Antimony EUV Photoresists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2021, 34, 117-121.	0.3	1
2	EUV Photochemistry of $\hat{I}\pm$ -Substituted Antimony Carboxylate Complexes. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2021, 34, 81-86.	0.3	0
3	ToF-SIMS analysis of antimony carboxylate EUV photoresists. , 2019, , .		1
4	Oligomers of MORE: Molecular Organometallic Resists for EUV. , 2019, , .		0
5	Isotopic Labeling Studies of EUV Photoresists Containing Antimony. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 233-242.	0.3	2
6	Polymer effects on PAG acid yield in EUV resists (Conference Presentation). , 2018, , .		4
7	Molecular organometallic resists for EUV (MORE): Reactivity as a function of metal center (Bi, Sb, Te) Tj ETQq1 1 0.784314 rgBT /Overlo		
8	Mechanisms of photodecomposition of metal-containing EUV photoresists: isotopic labelling studies. , 2018, , .		0
9	Antimony photoresists for EUV lithography: mechanistic studies. Proceedings of SPIE, 2017, , .	0.8	6
10	Advanced development techniques for metal-based EUV resists. Proceedings of SPIE, 2017, , .	0.8	6
11	Reactivity of metal-oxalate EUV resists as a function of the central metal. Proceedings of SPIE, 2017, , .	0.8	8
12	Analytical techniques for mechanistic characterization of EUV photoresists. Proceedings of SPIE, 2017, , .	0.8	6
13	EUV Mechanistic Studies of Antimony Resists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 121-131.	0.3	11
14	Platinum and palladium oxalates: positive-tone extreme ultraviolet resists. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2015, 14, 043511.	0.9	35
15	High-sensitivity molecular organometallic resist for EUV (MORE). Proceedings of SPIE, 2015, , .	0.8	30
16	Organometallic carboxylate resists for extreme ultraviolet with high sensitivity. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2015, 14, 043503.	0.9	25
17	Electrical Conduction and Reliability in Dual-Layered Graphene Heterostructure Interconnects. IEEE Electron Device Letters, 2014, 35, 1311-1313.	3.9	7